

Applicant(s): John Timothy Strom

METHOD AND PROCESS OF APPLYING THE ANALYSIS OF  
SCRUB MARK MORPHOLOGY AND LOCATION TO THE  
EVALUATION AND CORRECTION OF SEMICONDUCTOR  
TESTING, ANALYSIS, AND MANUFACTURE

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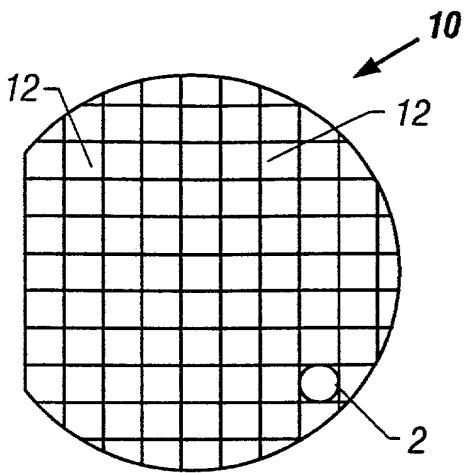


FIG. 1

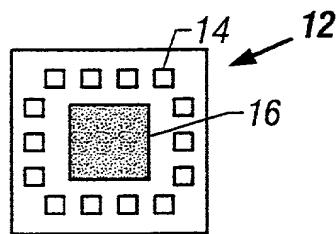


FIG. 2

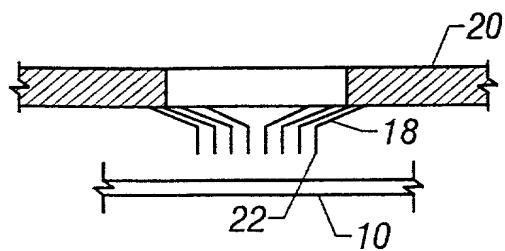


FIG. 3

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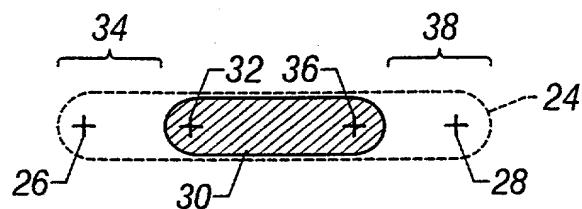


FIG. 4

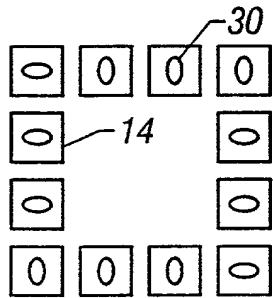


FIG. 5A

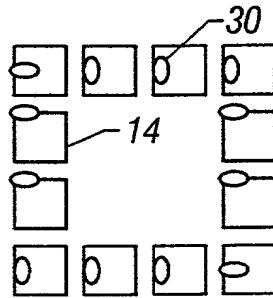


FIG. 5B

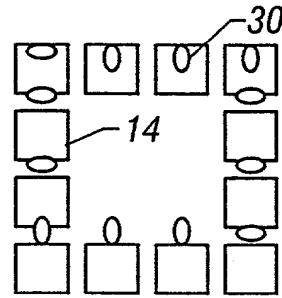


FIG. 5C

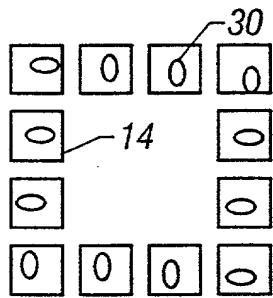


FIG. 5D

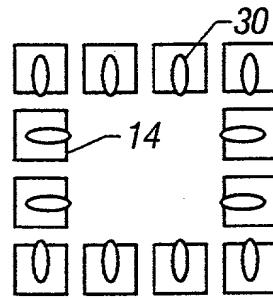


FIG. 5E

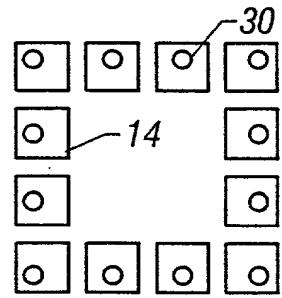


FIG. 5F

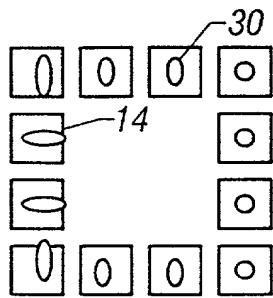


FIG. 5G

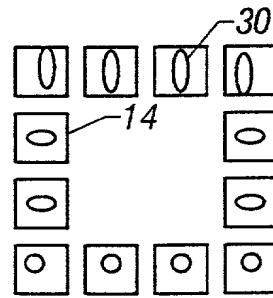


FIG. 5H

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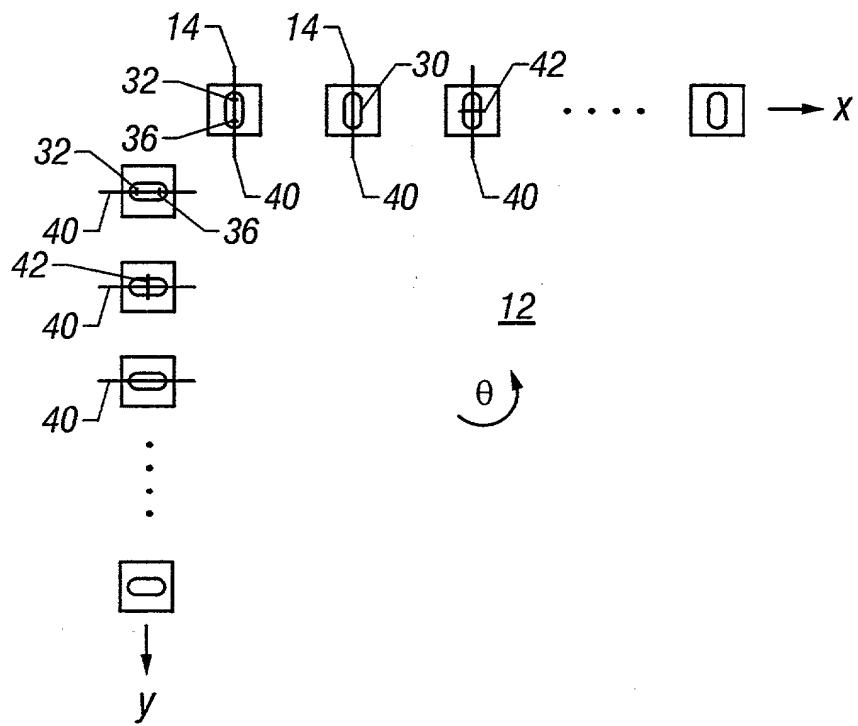


FIG. 6